

L Number	Hits	Search Text	DB	Time stamp
4	327	(waveguide near3 taper\$4) and (etch\$6 near8 ion) and mask	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:43
5	1	6015976.pn.	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:44
6	1	6015976.pn. and waveguide and ions	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:44
7	8197	(mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6))	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:49
8	21	((waveguide near3 taper\$4) and (etch\$6 near8 ion) and mask) and ((mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6)))	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:49
-	1	20030002793.pn.	USPAT; US-PGPUB; EPO; JPO	2004/03/15 19:51
-	13	4415227.pn. or 5078516.pn. or 5172143.pn. or 5265177.pn. or 5278926.pn. or 5439782.pn. or 5576149.pn. or 5629999.pn. or 5844929.pn. or 5854868.pn. or 5868952.pn. or 6108478.pn.	USPAT; US-PGPUB; EPO; JPO	2003/07/09 10:24
-	9767	385/14,28,37,43,49,50,129,130,131,132.ccls. or 65/386,403.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/07/09 10:28
-	414	(waveguide near3 taper\$4) and etch\$6 and mask	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:27
-	108267	385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls. and 372/\$6.ccls.	USPAT; US-PGPUB; EPO; JPO	2004/01/07 09:57
-	260	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls. and 372/\$6.ccls.) and ((waveguide near3 taper\$4) and etch\$6 and mask)	USPAT; US-PGPUB; EPO; JPO	2003/07/09 10:31
-	23	(waveguide near3 taper\$4) and etch\$6 and (mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6))	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:02
-	19	(waveguide near3 taper\$4) and etch\$6 and (mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6)) and ion	USPAT; US-PGPUB; EPO; JPO	2003/07/09 15:29
-	12	(waveguide near3 taper\$4) and etch\$6 and (mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6)) and ion and silicon	USPAT; US-PGPUB; EPO; JPO	2003/07/09 16:02
-	12	(waveguide near3 taper\$4) and etch\$6 and (mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6)) and ion and silicon and mask	USPAT; US-PGPUB; EPO; JPO	2003/07/09 16:03

-	190	(waveguide near3 taper\$4) and (diffraction near grating) and substrate	USPAT; US-PGPUB; EPO; JPO	2003/07/09 17:47
-	5	(waveguide near3 taper\$4 near vertical) and (diffraction near grating) and substrate	USPAT; US-PGPUB; EPO; JPO	2003/07/09 17:50
-	11	((waveguide near3 taper\$4) with (diffraction near grating)) and substrate	USPAT; US-PGPUB; EPO; JPO	2003/07/09 17:51
-	21	((waveguide near3 taper\$4) same (diffraction near grating)) and substrate	USPAT; US-PGPUB; EPO; JPO	2004/03/16 10:27
-	1	6292609.pn. and ion	USPAT; US-PGPUB; EPO; JPO	2004/01/07 09:39
-	1	6292609.pn. and ion and RIE	USPAT; US-PGPUB; EPO; JPO	2004/01/07 09:51
-	1	6292609.pn. and ion and RIE and "56"	USPAT; US-PGPUB; EPO; JPO	2004/01/07 09:52
-	112956	385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls. and 372/\$6.ccls.	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:25
-	3554	(ion near2 (etch\$6 or mill\$6)) and taper\$6 and mask	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:35
-	727	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls. and 372/\$6.ccls.) and ((ion near2 (etch\$6 or mill\$6)) and taper\$6 and mask)	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:02
-	7484	(mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6))	USPAT; US-PGPUB; EPO; JPO	2004/09/19 18:49
-	16	((385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls. and 372/\$6.ccls.) and ((ion near2 (etch\$6 or mill\$6)) and taper\$6 and mask)) and ((mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6)))	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:05
-	201951	385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls.	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:25
-	7484	(mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6))	USPAT; US-PGPUB; EPO; JPO	2004/03/15 19:52
-	21	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls.) and ((mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6))) and ((ion near2 (etch\$6 or mill\$6)) and taper\$6 and mask)	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:26

-	10728	etch\$6 and taper\$6 and mask	USPAT; US-PGPUB; EPO; JPO	2004/01/07 10:35
-	59	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls.) and ((mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6))) and (etch\$6 and taper\$6 and mask)	USPAT; US-PGPUB; EPO; JPO	2004/01/07 11:08
-	380	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls.) and (etch\$6 and taper\$6 and mask) and (taper\$6 near4 (waveguide or core))	USPAT; US-PGPUB; EPO; JPO	2004/01/07 11:09
-	209	(385/\$6.ccls. or 398/\$6.ccls. or 216/\$6.ccls. or 65/\$6.ccls. or 359/\$6.ccls.) and (etch\$6 and taper\$6 and mask) and (taper\$6 near4 (waveguide or core)) and ((ion near2 (etch\$6 or mill\$6)) and taper\$6 and mask)	USPAT; US-PGPUB; EPO; JPO	2004/01/08 09:15
-	1	6525296.pn. and (ion or RIE)	USPAT; US-PGPUB; EPO; JPO	2004/01/07 12:01
-	3	("5462700" "5726962" "6002515").PN.	USPAT	2004/01/07 12:04
-	3	6292609.URPN.	USPAT	2004/01/07 12:07
-	7	("4691982" "4693544" "4705346" "4737015" "4776655" "4778236" "4792200").PN.	USPAT	2004/01/07 12:08
-	6	4865407.URPN.	USPAT	2004/01/07 12:08
-	6	4865407.URPN.	USPAT	2004/01/07 12:12
-	148	(385/\$6.ccls. or 398/\$6.ccls.) and (taper\$6 near4 (waveguide or core)) and (diffraction near grating) and substrate	USPAT; US-PGPUB; EPO; JPO	2004/01/08 09:30
-	7685	(mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6))	USPAT; US-PGPUB; EPO; JPO	2004/03/15 19:52
-	67	(mask near2 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6)) and waveguide and (ion same (etch\$6 or mill\$6))	USPAT; US-PGPUB; EPO; JPO	2004/03/16 09:20
-	0	20010050271.URPN.	USPAT	2004/03/16 08:27
-	108	(mask near5 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6)) and waveguide and (ion same (etch\$6 or mill\$6))	USPAT; US-PGPUB; EPO; JPO	2004/03/16 11:26
-	22	((waveguide near3 taper\$4) same (diffraction near grating)) and substrate	USPAT; US-PGPUB; EPO; JPO	2004/03/16 10:27

-	1	(mask near5 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6)) and waveguide and (ion same (etch\$6 or mill\$6)) and 6015976.pn.	USPAT; US-PGPUB; EPO; JPO	2004/03/16 11:33
-	1	(mask near5 (mov\$6 or translat\$6 or oscillat\$4 or reciprecat\$6 and rotat\$6)) and waveguide and (ion same (etch\$6 or mill\$6)) and 6015976.pn. and (diffraction near grating)	USPAT; US-PGPUB; EPO; JPO	2004/03/16 11:33